Linda Milor

List of Publications by Year in descending order

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| 105 | 694 | 13 | 17 |
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| papers | citations | h-index | g-index |
| 106 | 106 | 106 | 274 |
| all docs | docs citations | times ranked | citing authors |

| # | Article | IF | CITATIONS |
|----|---|-----|-----------|
| 1 | A Comprehensive Framework for Analysis of Time-Dependent Performance-Reliability Degradation of SRAM Cache Memory. IEEE Transactions on Very Large Scale Integration (VLSI) Systems, 2021, 29, 857-870. | 2.1 | 3 |
| 2 | Inverse Design of FinFET SRAM Cells. , 2020, , . | | 1 |
| 3 | Optimal Accelerated Test Framework for Time-Dependent Dielectric Breakdown Lifetime Parameter Estimation. IEEE Transactions on Very Large Scale Integration (VLSI) Systems, 2020, 28, 2658-2671. | 2.1 | 2 |
| 4 | Optimal sampling for accelerated testing in 14Ânm FinFET ring oscillators. Microelectronics Reliability, 2020, 114, 113753. | 0.9 | 0 |
| 5 | Extraction of wearout model parameters using on-line test of an SRAM. Microelectronics Reliability, 2020, 114, 113756. | 0.9 | 1 |
| 6 | SRAM Stability Analysis and Performance–Reliability Tradeoff for Different Cache Configurations. IEEE Transactions on Very Large Scale Integration (VLSI) Systems, 2020, 28, 620-633. | 2.1 | 7 |
| 7 | Optimization of Experimental Designs for System- Level Accelerated Life Test in a Memory System Degraded by Time-Dependent Dielectric Breakdown. IEEE Transactions on Very Large Scale Integration (VLSI) Systems, 2019, 27, 1640-1651. | 2.1 | 5 |
| 8 | Impact of front-end wearout mechanisms on FinFET SRAM soft error rate. Microelectronics Reliability, 2019, 100-101, 113487. | 0.9 | 5 |
| 9 | A library based on deep neural networks for modeling the degradation of FinFET SRAM performance metrics due to aging. Microelectronics Reliability, 2019, 100-101, 113486. | 0.9 | 2 |
| 10 | Impact of Front-End Wearout Mechanisms on the Performance of a Ring Oscillator-Based Thermal Sensor. , 2019, , . | | 3 |
| 11 | Machine Learning for Detection of Competing Wearout Mechanisms. , 2019, , . | | 4 |
| 12 | Reliability and Accelerated Testing of 14nm FinFET Ring Oscillators. , 2019, , . | | 1 |
| 13 | Identification of Failure Modes for Circuit Samples with Confounded Causes of Failure. , 2019, , . | | 1 |
| 14 | Modeling of FinFET SRAM array reliability degradation due to electromigration. Microelectronics Reliability, 2019, 100-101, 113485. | 0.9 | 6 |
| 15 | Comprehensive Reliability-Aware Statistical Timing Analysis Using a Unified Gate-Delay Model for Microprocessors. IEEE Transactions on Emerging Topics in Computing, 2018, 6, 219-232. | 3.2 | 15 |
| 16 | New Electromigration Model and Its Potential Application on Degradation Simulation for FinFET SRAM. , 2018, , . | | 0 |
| 17 | Estimation of the Optimal Accelerated Test Region for FinFET SRAMs Degraded by Front-End and Back-End Wearout Mechanisms. , 2018, , . | | 3 |
| 18 | Optimal Accelerated Test Regions for Time- Dependent Dielectric Breakdown Lifetime Parameters Estimation in FinFET Technology. , 2018, , . | | 2 |

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| 19 | Lifetime Estimation Using Ring Oscillators for Prediction in FinFET Technology., 2018,,. | | 1 |
| 20 | Reliability and Aging Analysis on SRAMs Within Microprocessor Systems. , 2018, , . | | 1 |
| 21 | A Comprehensive Time-Dependent Dielectric Breakdown Lifetime Simulator for Both Traditional CMOS and FinFET Technology. IEEE Transactions on Very Large Scale Integration (VLSI) Systems, 2018, 26, 2470-2482. | 2.1 | 14 |
| 22 | Circuit-level reliability simulator for front-end-of-line and middle-of-line time-dependent dielectric breakdown in FinFET technology. , $2018, \ldots$ | | 6 |
| 23 | A methodology for estimating memory lifetime using a system-level accelerated life test and error-correcting codes. , 2017, , . | | 1 |
| 24 | An ECC-Assisted Postpackage Repair Methodology in Main Memory Systems. IEEE Transactions on Very Large Scale Integration (VLSI) Systems, 2017, 25, 2045-2058. | 2.1 | 5 |
| 25 | Negative Bias Temperature Instability and Gate Oxide Breakdown Modeling in Circuits With Die-to-Die Calibration Through Power Supply and Ground Signal Measurements. IEEE Transactions on Very Large Scale Integration (VLSI) Systems, 2017, 25, 2271-2284. | 2.1 | 6 |
| 26 | Adaptive supply voltage and duty cycle controller for yield-power optimization of ICs., 2017,,. | | 0 |
| 27 | Front-end of line and middle-of-line time-dependent dielectric breakdown reliability simulator for logic circuits. Microelectronics Reliability, 2017, 76-77, 81-86. | 0.9 | 9 |
| 28 | Analysis of errors in estimating wearout characteristics of time-dependent dielectric breakdown using system-level accelerated life test. Microelectronics Reliability, 2017, 76-77, 47-52. | 0.9 | 2 |
| 29 | Analysis of time-dependent dielectric breakdown induced aging of SRAM cache with different configurations. Microelectronics Reliability, 2017, 76-77, 87-91. | 0.9 | 7 |
| 30 | Memory reliability estimation degraded by TDDB using circuit-level accelerated life test. , 2017, , . | | 2 |
| 31 | A comparison study of time-dependent dielectric breakdown for analog and digital circuit's optimal accelerated test regions. , 2017, , . | | 3 |
| 32 | Modeling for SRAM reliability degradation due to gate oxide breakdown with a compact current model. , 2017 , , . | | 5 |
| 33 | A lifetime and power sensitive design optimization framework for a radio frequency circuit. , 2017, , . | | 3 |
| 34 | On-line monitoring of system health using on-chip SRAMs as a wearout sensor., 2017,,. | | 1 |
| 35 | Modeling of the reliability degradation of a FinFET-based SRAM due to bias temperature instability, hot carrier injection, and gate oxide breakdown., 2017,,. | | 5 |
| 36 | Design for reliability: A duty-cycle management system for timing violations. , 2016, , . | | 1 |

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| 37 | TDDB-emerald: A methodology for estimating memory reliability degradation resulting from time-dependent dielectric breakdown. , 2016 , , . | | 3 |
| 38 | SRAM stability analysis for different cache configurations due to Bias Temperature Instability and Hot Carrier Injection. , $2016, , .$ | | 18 |
| 39 | Online Measurement of Degradation Due to Bias Temperature Instability in SRAMs. IEEE Transactions on Very Large Scale Integration (VLSI) Systems, 2016, 24, 2184-2194. | 2.1 | 17 |
| 40 | Built-In Self-Test Methodology With Statistical Analysis for Electrical Diagnosis of Wearout in a Static Random Access Memory Array. IEEE Transactions on Very Large Scale Integration (VLSI) Systems, 2016, 24, 2521-2534. | 2.1 | 10 |
| 41 | System-Level Modeling of Microprocessor Reliability Degradation Due to Bias Temperature Instability and Hot Carrier Injection. IEEE Transactions on Very Large Scale Integration (VLSI) Systems, 2016, 24, 2712-2725. | 2.1 | 17 |
| 42 | Impact of stress acceleration on mixed-signal gate oxide lifetime. , 2015, , . | | 6 |
| 43 | Estimation of remaining life using embedded SRAM for wearout parameter extraction. , 2015, , . | | 3 |
| 44 | Microprocessor Aging Analysis and Reliability Modeling Due to Back-End Wearout Mechanisms. IEEE Transactions on Very Large Scale Integration (VLSI) Systems, 2015, 23, 2065-2076. | 2.1 | 18 |
| 45 | Comprehensive reliability and aging analysis on SRAMs within microprocessor systems. Microelectronics Reliability, 2015, 55, 1290-1296. | 0.9 | 15 |
| 46 | Impact of Linewidth on Backend Dielectric TDDB and Incorporation of the Linewidth Effect in Full Chip Lifetime Analysis. IEEE Transactions on Semiconductor Manufacturing, 2015, 28, 25-34. | 1.4 | 2 |
| 47 | Accurate standard cell characterization and statistical timing analysis using multivariate adaptive regression splines. , $2015, , .$ | | 10 |
| 48 | Processor-level reliability simulator for time-dependent gate dielectric breakdown. Microprocessors and Microsystems, 2015, 39, 950-960. | 1.8 | 8 |
| 49 | Panel: Analog/RF BIST: Are we there yet?. , 2015, , . | | 0 |
| 50 | MBIST and statistical hypothesis test for time dependent dielectric breakdowns due to GOBD vs. BTDDB in an SRAM array. , 2015 , , . | | 2 |
| 51 | System-level variation-aware aging simulator using a unified novel gate-delay model for bias temperature instability, hot carrier injection, and gate oxide breakdown. Microelectronics Reliability, 2015, 55, 1334-1340. | 0.9 | 25 |
| 52 | System-level modeling of microprocessor reliability degradation due to TDDB. , 2014, , . | | 1 |
| 53 | Diagnosis of resistive-open defects due to electromigration and stress-induced voiding in an SRAM array. , 2014, , . | | 4 |
| 54 | Memory BIST for on-chip monitoring of resistive-open defects due to electromigration and stress-induced voiding in an SRAM array. , 2014, , . | | 4 |

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| 55 | System-level modeling of microprocessor reliability degradation due to BTI and HCI., 2014, , . | | 21 |
| 56 | Simulation of system backend dielectric reliability. Microelectronics Journal, 2014, 45, 1327-1334. | 1.1 | 4 |
| 57 | Impact of die partitioning on reliability and yield of 3D DRAM. , 2014, , . | | 2 |
| 58 | Backend Dielectric Reliability Full Chip Simulator. IEEE Transactions on Very Large Scale Integration (VLSI) Systems, 2014, 22, 1750-1762. | 2.1 | 7 |
| 59 | Built-in self test methodology for diagnosis of backend wearout mechanisms in SRAM cells. , 2014, , . | | 6 |
| 60 | Gate oxide breakdown parameter extraction with ground and power supply signature measurements. , $2014, , .$ | | 3 |
| 61 | A Survey of Yield Modeling and Yield Enhancement Methods. IEEE Transactions on Semiconductor Manufacturing, 2013, 26, 196-213. | 1.4 | 21 |
| 62 | System-level modeling and reliability analysis of microprocessor systems. , 2013, , . | | 13 |
| 63 | Impact of NBTI/PBTIon SRAMs within microprocessor systems: Modeling, simulation, and analysis. Microelectronics Reliability, 2013, 53, 1183-1188. | 0.9 | 7 |
| 64 | System-Level Modeling and Microprocessor Reliability Analysis for Backend Wearout Mechanisms. , 2013, , . | | 22 |
| 65 | A Delay Evaluation Circuit for Analog BIST Function. IEICE Transactions on Electronics, 2013, E96.C, 393-401. | 0.3 | 0 |
| 66 | Backend dielectric chip reliability simulator for complex interconnect geometries. , 2012, , . | | 11 |
| 67 | Impact of NBTI on analog components. , 2012, , . | | 0 |
| 68 | Analysis and On-Chip Monitoring of Gate Oxide Breakdown in SRAM Cells. IEEE Transactions on Very Large Scale Integration (VLSI) Systems, 2012, 20, 855-864. | 2.1 | 15 |
| 69 | A comparative study of wearout mechanisms in state-of-art microprocessors. , 2012, , . | | 8 |
| 70 | Wearout-aware compiler-directed register assignment for embedded systems. , 2012, , . | | 4 |
| 71 | Backend dielectric reliability simulator for microprocessor system. Microelectronics Reliability, 2012, 52, 1953-1959. | 0.9 | 4 |
| 72 | NBTI resistant SRAM design. , 2011, , . | | 17 |

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| 73 | Impact of irregular geometries on low-k dielectric breakdown. Microelectronics Reliability, 2011, 51, 1582-1586. | 0.9 | 1 |
| 74 | Determining the Impact of Within-Die Variation on Circuit Timing. IEEE Transactions on Semiconductor Manufacturing, 2011, 24, 385-391. | 1.4 | 5 |
| 75 | Backend low-k TDDB chip reliability simulator. , 2011, , . | | 20 |
| 76 | Methodology to determine the impact of linewidth variation on chip scale copper/low-k backend dielectric breakdown. Microelectronics Reliability, 2010, 50, 1341-1346. | 0.9 | 21 |
| 77 | Via wearout detection with on-chip monitors. Microelectronics Journal, 2010, 41, 789-800. | 1.1 | 2 |
| 78 | Reliable cache design with on-chip monitoring of NBTI degradation in SRAM cells using BIST., 2010,,. | | 39 |
| 79 | Area Scaling for Backend Dielectric Breakdown. IEEE Transactions on Semiconductor Manufacturing, 2010, 23, 429-441. | 1.4 | 15 |
| 80 | Towards a chip level reliability simulator for copper/low-k backend processes. , 2010, , . | | 17 |
| 81 | Analysis of the impact of linewidth variation on low-k dielectric breakdown. , 2010, , . | | 9 |
| 82 | Ring oscillator based embedded structure for decoupling PMOS/NMOS degradation with switching activity replication. , 2010, , . | | 4 |
| 83 | TDDB chip reliability in copper interconnects. , 2010, , . | | 1 |
| 84 | Reliable cache design with detection of gate oxide breakdown using BIST., 2009,,. | | 3 |
| 85 | On chip monitoring of via degradation. , 2009, , . | | 0 |
| 86 | Timing Analysis with Compact Variation-Aware Standard Cell Models. , 2009, , . | | 2 |
| 87 | A methodology to extract failure rates for low-k dielectric breakdown with multiple geometries and in the presence of die-to-die linewidth variation. Microelectronics Reliability, 2009, 49, 1096-1102. | 0.9 | 15 |
| 88 | Timing analysis with compact variation-aware standard cell models. The Integration VLSI Journal, 2009, 42, 312-320. | 1.3 | 1 |
| 89 | Modeling Low-k Dielectric Breakdown to Determine Lifetime Requirements. IEEE Design and Test of Computers, 2009, 26, 18-27. | 1.4 | 14 |
| 90 | A DLL Design for Testing I/O Setup and Hold Times. IEEE Transactions on Very Large Scale Integration (VLSI) Systems, 2009, 17, 1579-1592. | 2.1 | 13 |

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| 91 | Via wearout detection with on chip monitors. , 2009, , . | | 3 |
| 92 | Determination of the impact of field enhancement in low-k dielectric breakdown., 2009,,. | | 1 |
| 93 | Fast Variation-Aware Statistical Dynamic Timing Analysis. , 2009, , . | | 1 |
| 94 | Diagnosis of Optical Lithography Faults With Product Test Sets. IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems, 2008, 27, 1657-1669. | 1.9 | 3 |
| 95 | A BIST Circuit for DLL Fault Detection. IEEE Transactions on Very Large Scale Integration (VLSI) Systems, 2008, 16, 1687-1695. | 2.1 | 3 |
| 96 | BIST for testing of delay., 2007,,. | | 0 |
| 97 | Modeling of the breakdown mechanisms for porous copper/low-k process flows. Microelectronics Reliability, 2007, 47, 1478-1482. | 0.9 | 6 |
| 98 | Backend dielectric breakdown dependence on linewidth and pattern density. Microelectronics Reliability, 2007, 47, 1473-1477. | 0.9 | 9 |
| 99 | Porosity-Induced Electric Field Enhancement and Its Impact on Charge Transport in Porous Inter-Metal Dielectrics., 2006,,. | | 2 |
| 100 | Study of Area Scaling Effect on Integrated Circuit Reliability Based on Yield Models. Microelectronics Reliability, 2005, 45, 1305-1310. | 0.9 | 9 |
| 101 | Characterization of spatial CD variability, spatial mask-level correction, and improvement of circuit performance., 2000,,. | | 2 |
| 102 | Proximity effect correction for clock-rate maximization. , 1998, 3510, 82. | | 1 |
| 103 | Application of rigorous topography simulation for modeling of defect propagation/growth in VLSI fabrication. , $1997, \ldots$ | | 0 |
| 104 | Modeling of defect propagation/growth for yield impact prediction in VLSI manufacturing. Proceedings of SPIE, 1997, , . | 0.8 | 5 |
| 105 | Impact of CD control on circuit yield in submicron lithography. , 1992, 1671, 357. | | 4 |